

**Amendments to the Specification:**

Please amend the Abstract of the Disclosure on page 32 of the Specification as follows:

A method of manufacturing a stamper/imprinter for use in patterning of a recording medium, comprises sequential steps of: \_\_\_\_\_

\_\_\_\_\_ (a) \_\_\_\_\_ providing a substrate/workpiece comprising: \_\_\_\_\_

\_\_\_\_\_ (i) \_\_\_\_\_ a topographical pattern formed in a portion of a surface \_\_\_\_\_

\_\_\_\_\_ of the substrate/workpiece, the pattern defining a periphery; and \_\_\_\_\_

\_\_\_\_\_ (ii) \_\_\_\_\_ an alignment mark formed in another portion of the \_\_\_\_\_

\_\_\_\_\_ surface of surrounding the periphery; \_\_\_\_\_

\_\_\_\_\_ (b) \_\_\_\_\_ forming an opaque protective film overlying the entirety of the surface; \_\_\_\_\_

\_\_\_\_\_ (c) \_\_\_\_\_ removing a peripheral portion of the protective film to expose the alignment mark;

\_\_\_\_\_ (d) \_\_\_\_\_ removing selected portions of the substrate/workpiece while utilizing the alignment mark for accurate alignment during the removal process; and \_\_\_\_\_

\_\_\_\_\_ (e) \_\_\_\_\_ removing remaining portions of the protective film prior to use comprising the sequential steps of providing a substrate/workpiece comprising a topographical pattern formed in a portion of a surface of the substrate/workpiece. The pattern defines a periphery. An alignment mark is formed in another portion of the surface of surrounding the periphery. An opaque protective film is formed overlying the entirety of the surface. A peripheral portion of the protective film is removed to expose the alignment mark. Selected portions of the substrate/workpiece are removed while the alignment mark is utilized for accurate alignment during the removal process. Remaining portions of the protective film are removed prior to use.